

Film Thickness by Thin Film FP Method -**ElementEye JSX-1000S**

Introduction

Surface treatments such as plating are applied to parts to impart corrosion resistance, decoration, and functionality. Since the thickness of these films relates to product characteristics, quality, and production cost, it is important to control. JEOL's X-ray fluorescence spectrometer can perform non-destructive measurement of film thickness (up to 5 layers). Using our advanced FP method, standards are not required.

Thin Film Measurement Examples

Au Plating

Sample



Measurement Condition

Tube Voltage: 50 kV Collimator Dia: 0.9 mm Atmosphere : Air Measurement Time: 60sec

Spectrum 0.9 0.7 0.6 0.3 0.2

Analysis Result

Analysis Result
(μm)
2.06

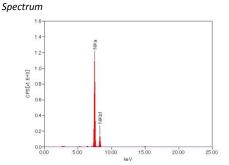
Ni Plating

Sample

Measurement Condition

Tube Voltage: 50 kV Collimator Dia: 0.9 mm Atmosphere : Air

Measurement Time: 60sec



Analysis Result

Certified Value	Analysis Result
(μm)C	(μm)
0.99	1.10

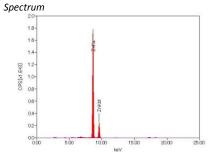
Zn Plating

Sample



Measurement Condition

Tube Voltage: 50 kV Collimator Dia: 0.9 mm Atmosphere: Air Measurement Time: 60sec



Analysis Result

Certified Value	Analysis Result
(μm)	(μ m)
2.61	2.81

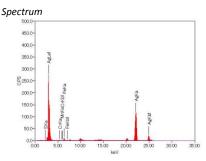
Ag Plating

Sample



Measurement Condition

Tube Voltage: 50 kV Collimator Dia: 0.9 mm Atmosphere: Air Measurement Time: 60sec



Analysis Result

Certified Value $(\mu \mathrm{m})$	Analysis Result $(\mu \mathrm{m})$
8.97	8.89